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| Substitute for form 1449A/PTO & 1449B/PTO FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT <small>(use as many sheets as necessary)</small> | | | | Complete if Known | |
| | | Application Number | | 10/764,407 | |
| | | Filing Date | | January 23, 2004 | |
| | | First Named Inventor | | Shenggao Liu et al. | |
| | | Examiner Name | | | |
| | | Attorney Docket Number | | 005950-844 | |
| Sheet | 3 | of | 3 | | |

FOREIGN PATENT DOCUMENTS

NON-PATENT LITERATURE DOCUMENTS

| Examiner Initials | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. |
|-------------------|---|
| GJ | LIAW, Der-Jang, "Synthesis and characterization of new polyamides and polyimides prepared from 2,2-bis[4-(4-aminophenoxy)phenyl]adamantane," <i>Macromol. Chem. Phys.</i> 200, No. 6, pp. 1326-1332 (1999) |
| GJ | NOZAKI, Koji et al., "High-Performance Resist Materials for ArF Excimer Laser and Electron Beam |
| GJ | Lithography," <i>FUJITSU Sci Tech. J.</i> , 38, 1, pp. 3-12 (June 2002) |
| GJ | PADMANABAN, Munirathna, et al., "Etch Properties of 193nm Resists: Issues and Approaches," <i>Journal of Photopolymer Science and Technology</i> , Vol 15, No. 3 (2002), pp. 521-528 |
| GJ | PADMANABAN, Munirathna, et al., "Layer-Specific Resists for 193nm Lithography," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp. 607-616 |
| GJ | PANIEZ, P. J., et al., "Thermal Phenomena in Acrylic 193 nm Resists," <i>SPIE Conferences on Advances in Resist Technology and Processing XVI</i> , Santa Clara, CA, <i>SPIE</i> Vol. 3678 pp. 1352-1363 JUNE 1999 /CH/ 10/1/08 |
| GJ | SHIDA, Naomi, "Advanced Materials for 193-nm Resists," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp. 601-606 |
| GJ | USHIROGOUCHI, Tohru, et al., "Advanced Materials for 193-nm Resists," In <i>Advances in Resist Technology and Processing XVII</i> , Francis M. Houlahan, Editor, <i>Proceedings of SPIE</i> Vol. 3999 (2000) pp. 1147-1156 |

**Examiner
Signature**

~~Date Considered~~

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.